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| | Applicant(s) | Conf. No. |
| (Use several sheets if necessary) | Ibrahim Abdulhalim, et al. | 9738 |
| | Filing Date | Group |
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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